

ABSTRACT

**Device Manufacturing Method, Mask
and Device**

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A method for use in manufacturing CCD or CMOS image sensors in which a substrate covered in a layer of colored radiation sensitive material has a patterned beam of radiation projected onto it. The patterned beam of radiation includes a pattern for forming device features in areas of a product die and a pattern for use in forming features of an alignment mark in other areas. This avoids the
10 difficulty of aligning on alignment marks which are below a colored resist.

Fig. 5a